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L Number	Hits	Search Text	DB	Time stamp
1	5295	(250/492.2,504R,492.1).CCLS.	USPAT; US-PGPUB;	2004/09/26 00:57
2	3764	(extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)	EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/09/26 00:58
3	2517	((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/09/26 01:45
4	494	(((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:46
5	480	or debris) ((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:01
6	380	sample) (((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:01
7	111	sample)) and project\$5 ((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or sample)) and project\$5) and electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:01
8	74	<pre>((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or sample)) and project\$5) and electrode) and collect\$8</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:02
9	12	·	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:47
10	222		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/09/26 01:45

11	193	(((extreme adj ultraviolet) or EUV or	USPAT;	2004/09/26
11	193		US-PGPUB;	01:46
		extreme-ultraviolet or (extreme adj	· ·	01:46
		ultra-violet)) and	EPO; JPO;	
		((250/492.2,504R,492.1).CCLS.)) and (mask	DERWENT;	
	!	or reticle or (pattern\$4 near1	IBM_TDB	
		structure))		0004/00/06
12	79	((((extreme adj ultraviolet) or EUV or	USPAT;	2004/09/26
		extreme-ultraviolet or (extreme adj	US-PGPUB;	01:46
		ultra-violet)) and	EPO; JPO;	
		((250/492.2,504R,492.1).CCLS.)) and (mask	DERWENT;	
		or reticle or (pattern\$4 near1	IBM_TDB	
		structure))) and (by-product\$4 or		
	1	pollut\$5 or contamin\$4 or debris)		
13	4	((((extreme adj ultraviolet) or EUV or	USPAT;	2004/09/26
		extreme-ultraviolet or (extreme adj	US-PGPUB;	01:46
		ultra-violet)) and	EPO; JPO;	
		((250/492.2,504R,492.1).CCLS.)) and (mask	DERWENT;	
	1	or reticle or (pattern\$4 near1	IBM_TDB	
	1	structure))) and (by-product\$4)	-	
14	36	1 · · · · · · · · · · · · · · · · · · ·	USPAT;	2004/09/26
		or extreme-ultraviolet or (extreme adj	US-PGPUB;	02:28
		ultra-violet)) and (mask or reticle or	EPO; JPO;	
		(pattern\$4 near1 structure))) and	DERWENT;	
	İ	(by-product\$4 or pollut\$5 or contamin\$4	IBM TDB	
		or debris)) and (substrate or wafer or	<u>-</u>	
		sample)) and project\$5) and electrode)		
		and collect\$8) and (plasma with		
		(by-product\$4 or pollut\$5 or contamin\$4	!	
		or debris))		
15	14	I	USPAT;	2004/09/26
13	14	or extreme-ultraviolet or (extreme adj	US-PGPUB;	02:29
		ultra-violet)) and (mask or reticle or	EPO; JPO;	02.23
		(pattern\$4 near1 structure))) and	DERWENT;	
		(by-product\$4 or pollut\$5 or contamin\$4	IBM TDB	
	1	or debris)) and (substrate or wafer or	***-***	
		sample)) and project\$5) and electrode)		
			1	
		and collect\$8) and (plasma with		1
		(by-product\$4 or pollut\$5 or contamin\$4		
		or debris))) and		
		((250/492.2,504R,492.1).CCLS.)	IICDAM.	2004/09/26
16	3	((((((((extreme adj ultraviolet) or EUV	USPAT;	· · ·
		or extreme-ultraviolet or (extreme adj	US-PGPUB;	02:29
		ultra-violet)) and (mask or reticle or	EPO; JPO;	
		(pattern\$4 near1 structure))) and	DERWENT;	ĺ
		(by-product\$4 or pollut\$5 or contamin\$4	IBM_TDB	!
		or debris)) and (substrate or wafer or		1
	•	sample)) and project\$5) and electrode)		
		and collect\$8) and (plasma with		
	1	(by-product\$4 or pollut\$5 or contamin\$4		
		or debris))) and (particle with mov\$6)		<u> </u>